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#4 KDuncan  
5.16.02

PATENT  
ATTORNEY DOCKET NO.: 054216-5024

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Application of: )  
Ki Seog KIM et al. )  
Application No.: 10/029,390 ) Group Art Unit: Unknown  
Filed: December 28, 2001 ) Examiner: Unknown  
For: TEST PATTERN FOR MEASURING )  
CONTACT RESISTANCE AND )  
METHOD OF MANUFACTURING )  
THE SAME )

Commissioner for Patents  
Washington, D.C. 20231

Sir:

**PRELIMINARY AMENDMENT**

Prior to the examination of the above-identified application, please amend the  
above-identified application as follows:

**IN THE CLAIMS:**

Please replace claims 1-17, with the following:

- 91 1.(Amended) A test pattern for measuring a contact resistance, comprising:  
a test wafer in which a plurality of device isolation <sup>areas</sup> ~~films~~ <sup>object</sup> are formed to  
define a plurality of active regions;  
a plurality of interconnection diffusion layers formed in a word line region <sup>112</sup>  
crossing the plurality of device isolation <sup>areas</sup> ~~films~~ <sup>object</sup> and the plurality of active regions;  
<sup>parallel</sup>  
<sup>112</sup>